

Notice of References Cited

Application/Control No.

09/761,753

Applicant(s)/Patent Under
Reexamination
ISHIDA ET AL.

Examiner

Fernando Toledo

Art Unit

2823

Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-5202274-A	04-1993	Bae et al.	437/40
	B	US-6338991-B1	01-2002	Zhang et al.	438/162
	C	US-5915172-A	06-1999	Noumi et al.	438/151
	D	US-5170244-A	12-1992	Dohjo et al.	257/72
	E	US-5942767-A	08-1999	Na et al.	257/59
	F	US-5990492-A	11-1999	Kim	257/59
	G	US-6331356-B1	12-2001	Angelopoulos et al.	428/411.1
	H	US-5970326-A	10-1999	Lawley et al.	438/158
	I	US-5990986-A	11-1999	Song et al.	349/43
	J	US-5028551-A	07-1991	Dohjo et al.	437/41
	K	US-6087648-A	07-2000	Zhang et al.	250/208.1
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	JP-3-38622-A ✓	02-1991	Japan		
	O	JP-10-268347-A ✓	10-1998	Japan		
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	✓ Wolf and Tauber; Silicon Processing for the VLSI Era Volume 1: Process Technology, pp. 332, 452 - 453; Lattice Press 1986; Sunset Beach, California
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.